

ABSTRACT

Fe-Pt-C BASED SPUTTERING TARGET

5 Provided is a sintered sputtering target having a composition by atomic ratio represented by the formula: $(\text{Fe}_{100-X}\text{-Pt}_X)_{100-A}\text{C}_A$ (wherein A and X satisfy $20 \leq A \leq 50$ and $35 \leq X \leq 55$, respectively), wherein C particles are finely dispersed in a matrix alloy, and an oxygen content is 300 wt ppm or less. An object of the present invention is to provide an Fe-Pt based sputtering target having finely dispersed C particles and a low oxygen content, which allows manufacture of a granular structure magnetic thin film having excellent corrosion resistance, and further allows facilitation of ordering the L1_0 structure.

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Fig. 1